



The Fine Line: Summer 2016 Videos for the eBeam Community

Shot Talk

Aki Fujimura, CEO of D2S, recaps the emerging lithography trends presented at Photomask Japan and the agenda for the upcoming eBeam Initiative Taiwan seminar in June, as well as new developments in GPU-accelerated computing for mask making.



Leo Pang, chief product officer of D2S, also reviews these developments in [Chinese](#) including highlights of the recent China Semiconductor Technology International Conference.



Tech Talk

Naoya Hayashi of DNP examines both challenges and progress with nanoimprint lithography (NIL) master templates—including CD uniformity, image placement and defectivity—as well as evaluates VSB and multi-beam mask writing (MBMW) performance on 1X-nm master templates.



Perspectives

Aki Fujimura shares his viewpoint on why MBMW has become the most important development to the mask industry since VSB writing was introduced 15 years ago—and how all lithography paths lead to multi-beam.



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Video Archive

The Fine Line: Spring 2016 Edition



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[Aki Fujimura of D2S](#)



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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please email requests@ebeam.org or visit www.ebeam.org